Si monitoring tool

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Vertex Lxy resolution is now around 80 μm ,which was around 50 μm in Run 1. Before checking geometry data, I just checked the residual distribution after production process. Overall status is also checked by using ClusterMonitor.

1. **TrackMonitor module in Production job**

    - module MyPro is made removing modules in Production job except tracking part.
    - MyPro is at nkek09:~/ryuichi/my4.4/MyPro.
    - residual and impact parameter can be monitored using ~/ryuichi/my4.4/results/myButton.C

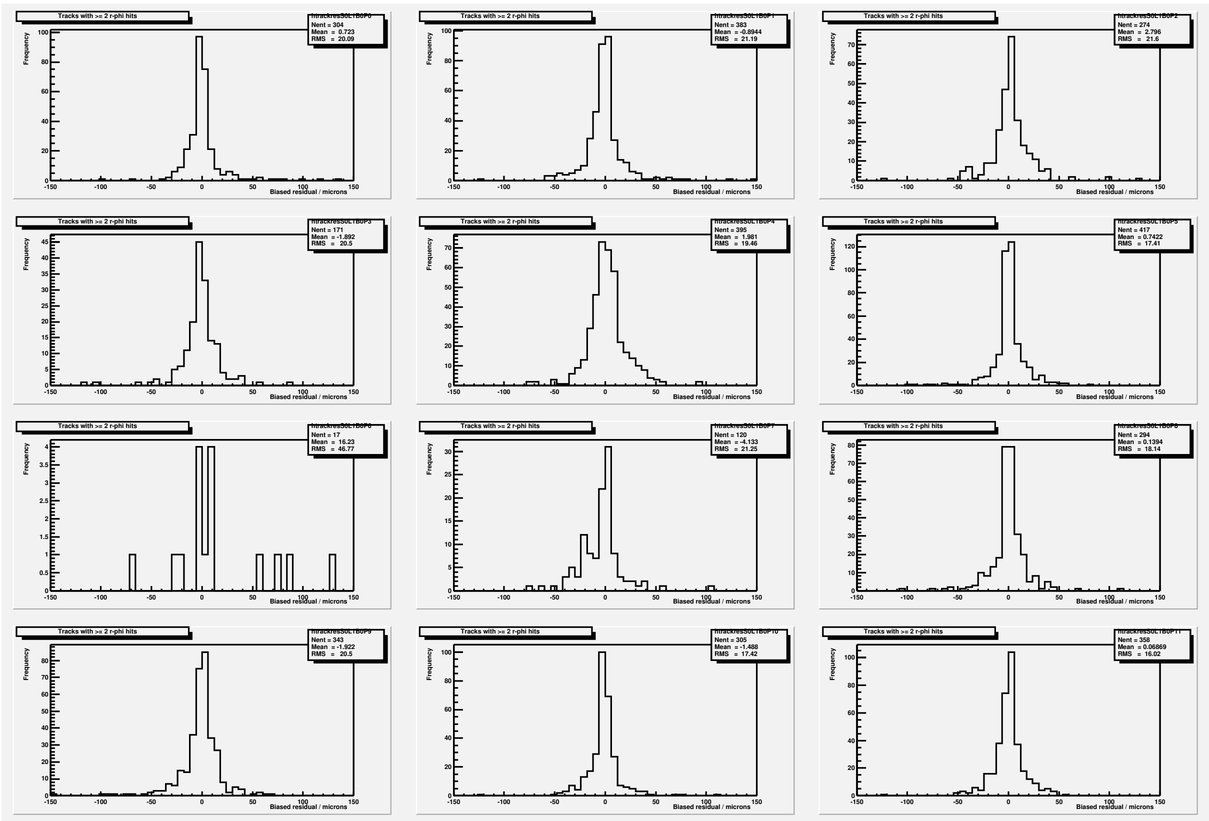

Figure 1: layer 1 residuals for each phi ladder

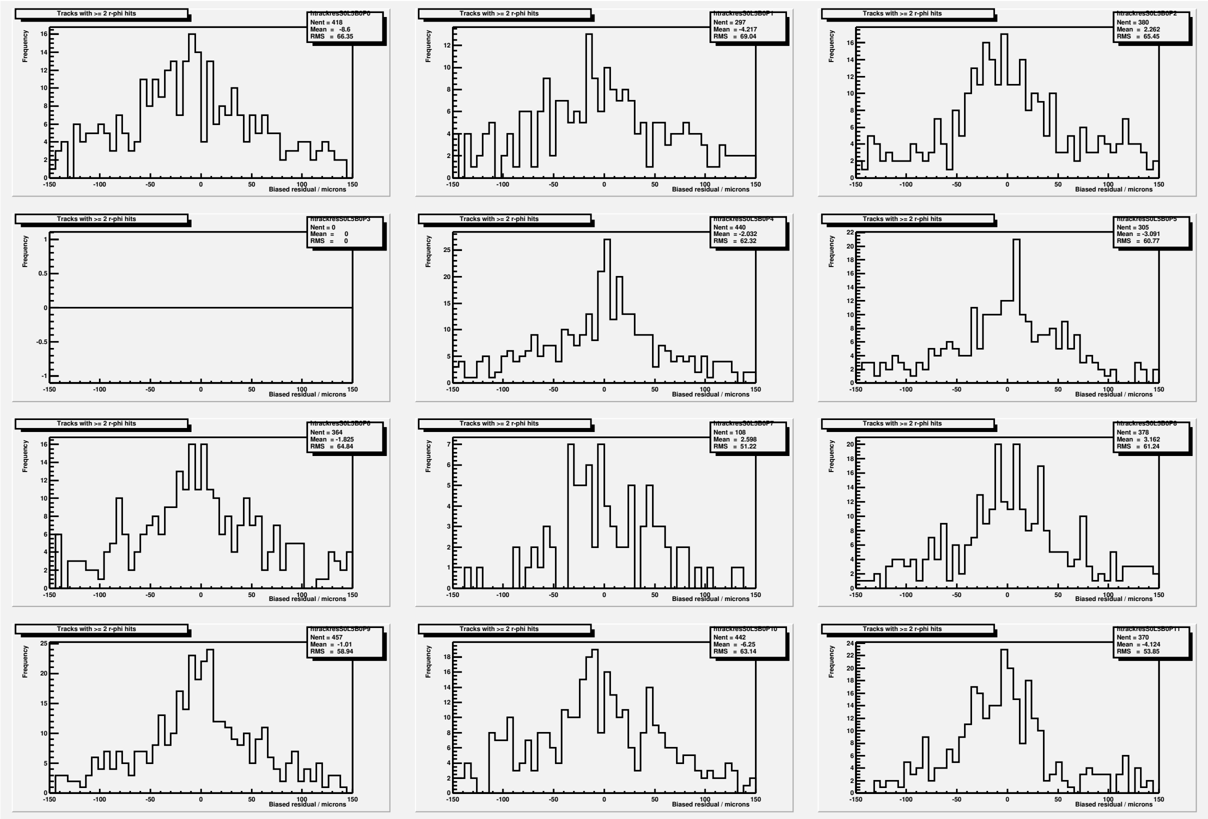

Figure 2: layer 5 residuals for each phi ladder

2. **ClusterMonitor module in SiliMon**

   - TProfie(2-d histo projection) is used to monitor mean ADC count for each chip
   - central barrel looks good. But others have a lot of not working chips.
   - monitor scripts are in fcdfsgi2:/cdf/scratch/ryuichi/mySil4.4/results

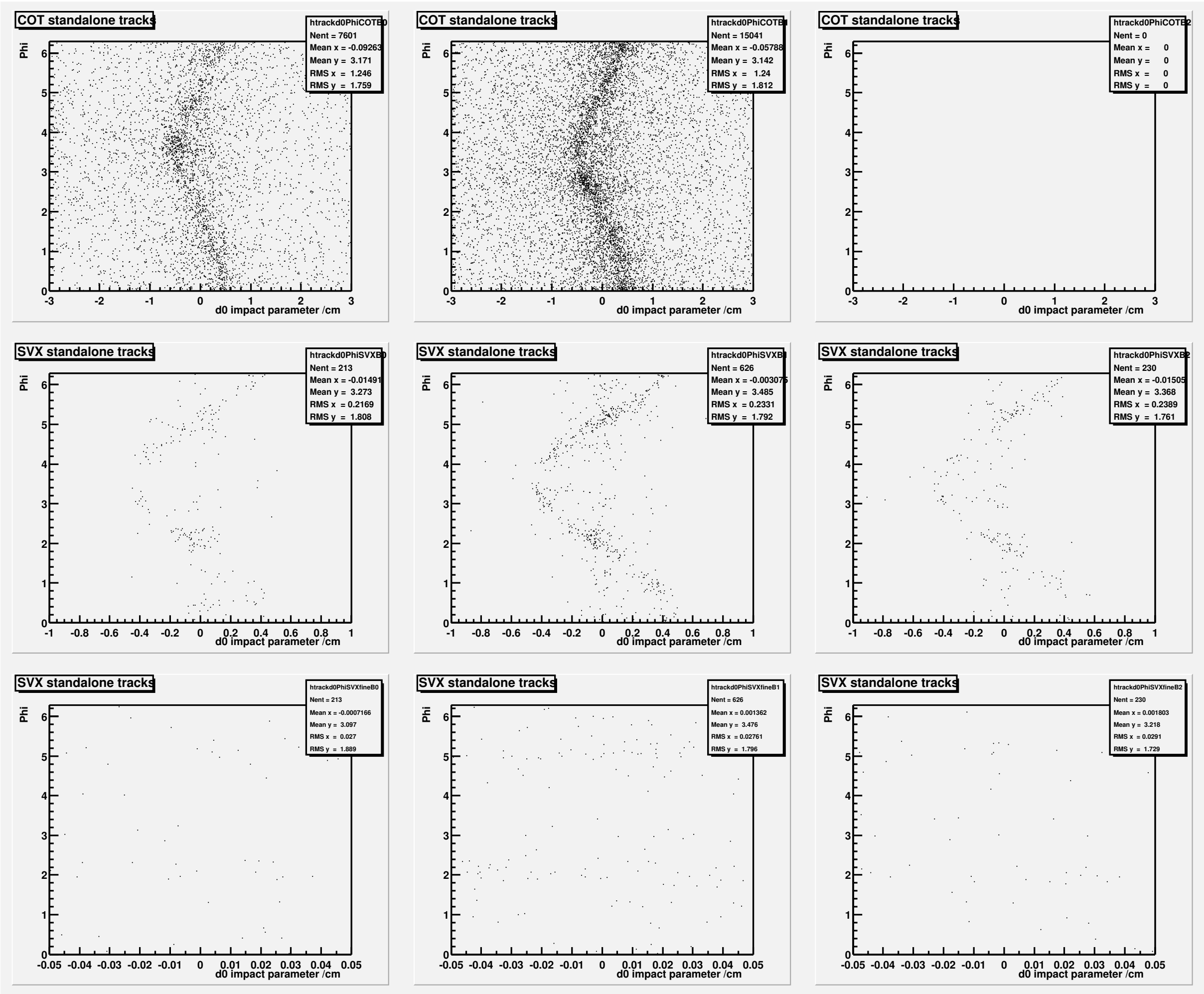

Figure 3: impact parameter vs phi

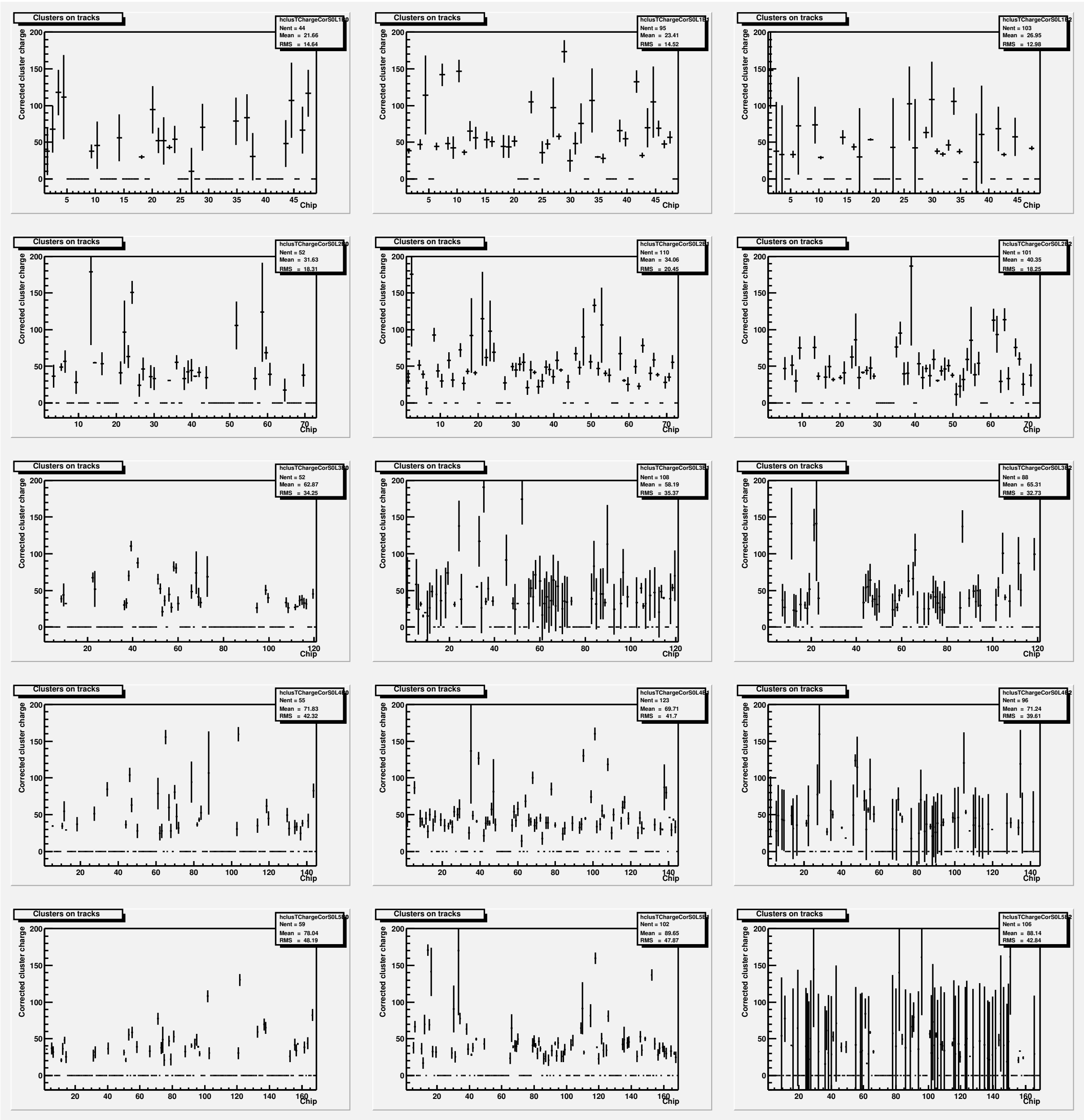

Figure 4: phi-side SVX mean corrected ADC count for each chip. Mean ADC count is divided by intersection length. left column:barrel 0,center column:barrel 1, right column:barrel 2. 1st row:layer 1, etc.

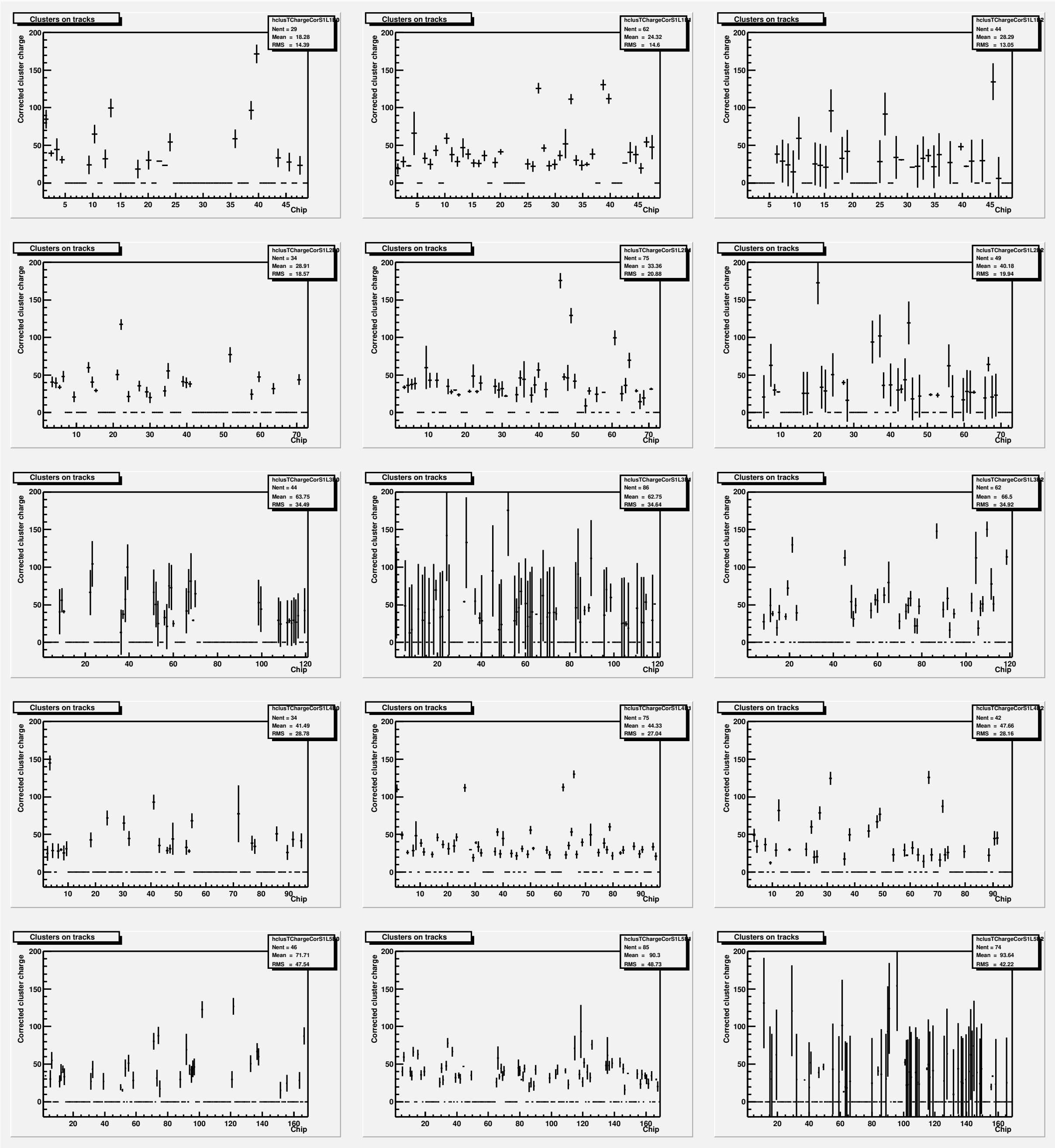

Figure 5: stereo-side SVX mean corrected ADC count for each chip. left column:barrel 0,center column:barrel 1, right column:barrel 2. 1st row:layer 1, etc.